

layer, wherein a phase shift of an odd multiple of at least 3 multiplied by 180° exists between a first reflection of the exposure light from an interface between the photoresist layer and the antireflective layer and a second reflection of the exposure light from an interface between the antireflective layer and the first layer, the first reflection having almost the same intensity as the second reflection to thereby substantially cancel the first and second reflections.

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END

62. (New) A substrate processing system comprising:
- means for flowing selected deposition gases into a substrate processing chamber at deposition gas flow rates;
 - means for adding a flow of an inert gas to the selected deposition gases at a flow rate previously determined to achieve a desired low deposition rate from a reaction of the selected deposition gases, said desired low deposition rate being lower than a deposition rate using said selected deposition gases at said deposition gas flow rates with a lower flow rate of said inert gas; and
 - means for depositing a thin film at said low deposition rate from said reaction of said deposition gases.

REMARKS

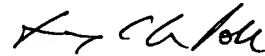
Claims 1-10 and 44-62 are pending. Claims 53 and 54 have been amended to correct informalities. New claims 55-62 have been added. It appears that page 1 of the specification might have been inadvertently omitted in the subject divisional application as filed. Applicants submit a copy of page 1 from the parent application as attached herewith, and respectfully request that it be entered into record. No new matter has been introduced.

CONCLUSION

Applicants believe all claims now pending in this Application are in condition for allowance. The issuance of a formal Notice of Allowance at an early date is respectfully requested.

If the Examiner believes a telephone conference would expedite prosecution of this application, please telephone the undersigned at 650-326-2400.

Respectfully submitted,



Chun-Pok Leung
Reg. No. 41,405

TOWNSEND and TOWNSEND and CREW LLP
Tel: (415) 576-0200; Fax: (415) 576-0300
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